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Application Number	09/920,341
Filing Date	08/01/01
First Named Inventor	Choi et al.
Group Art Unit	1724
Examiner Name	Unassigned
Attorney Docket Number	PA17-07V06

U.S. PATENT DOCUMENTS

FOREIGN PATENT DOCUMENTS

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Date
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**INFORMATION DISCLOSURE
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OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
SN	C18	LIN, "Multi-Layer Resist Systems", Introduction of Microlithography, American Chemical Society, 1983, pp. 287-350, IBM T.J. Watson Research Center, Yorktown Heights, New York 10598.	
SN	C19	COWIE, "Polymers: Chemistry and Physics of Modern Materials", 1991, pp. 408-409, 2 nd Ed, Chapman and Hall, a division of Routledge, Chapman and Hall, Inc., 29 West 35 th Street, NY, NY 10001-2291.	
SN	C20	CHOU et al., "Imprint of Sub-25 nm Vias and Trenches in Polymers", Applied Physics Letters, November 20, 1995, pp. 3114-3116, vol. 67(21).	
SN	C21	CHOU et al., "Imprint Lithography with 25-Nanometer Resolution", Science, Apr. 5, 1996, pp. 85-87, vol. 272.	
SN	C22	CHOU et al., "Imprint Lithography with Sub-10nm Feature Size and High Throughput", Microelectronic Engineering, 1997, pp. 237-240, vol. 35.	
SN	C23	XIA et al., "Soft Lithography", Agnew. Chem. Int. Ed., 1998, pp. 550-575, vol. 37.	

Examiner Signature	<i>Langley</i>	Date Considered	08/05/04
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